

	Type	Hits	Search Text	DBs
1	IS&R	4	((("5384270") or ("5814859")).PN.	US-PGPUB; USPAT; EPO; JPO; DERVENT; IBM_TDB
2	BRS	238850	"438"\$.ccls. (MOSFET)	US-PGPUB; USPAT; EPO; JPO; DERVENT; IBM_TDB
3	BRS	104	S2 and (silicon adj carbide adj MOSFET)	US-PGPUB; USPAT; EPO; JPO; DERVENT; IBM_TDB
4	BRS	22	S3 and (vertical adj MOSFET)	US-PGPUB; USPAT; EPO; JPO; DERVENT; IBM_TDB
5	BRS	239138	"438"\$.ccls. (MOSFET)	US-PGPUB; USPAT; EPO; JPO; DERVENT; IBM_TDB

	Type	Hits	Search Text	DBs
6	BRS	54	S5 and (silicon adj carbide adj MOSFET) and (ion adj implantation)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
7	BRS	2	S6 and (ion adj implantation adj mask)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
8	BRS	34	S6 and range	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
9	BRS	0	S6 and (ion adj implantation adj range)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
10	BRS	239138	"438"/\$.ccls. (MOSFET)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Type	Hits	Search Text	DBs
11	BRS	0	S10 and (silicon adj carbide adj MOSFET) and (implantation adj angle)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
12	BRS	104	S10 and (silicon adj carbide adj MOSFET)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
13	BRS	0	S13 and (angle adj of adj implantation)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
14	BRS	54	S12 and (ion adj implantation)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
15	BRS	36155	"438"\$.ccls. and (angloe of implantation)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Type	Hits	Search Text	DBs
16	BRS	47516	"438"/\$.ccls. and (angle of implantation)	US-PGPUB; USPAT; EPO; JPO; DERVENT; IBM_TDB
17	BRS	0	S16 and (silicon adj carbide adj MOSFET)	US-PGPUB; USPAT; EPO; JPO; DERVENT; IBM_TDB
18	BRS	7447	S16 and (MOSFET)	US-PGPUB; USPAT; EPO; JPO; DERVENT; IBM_TDB
19	BRS	475	S18 and (SiC)	US-PGPUB; USPAT; EPO; JPO; DERVENT; IBM_TDB
20	BRS	37	S19 and (vertical adj MOSFET)	US-PGPUB; USPAT; EPO; JPO; DERVENT; IBM_TDB